

IN THE CLAIMS

The following is a complete listing of the claims, and replaces all earlier versions and listings.

1-42. (Canceled)

43. (Previously Presented) A method for manufacturing a spacer which defines an interval between substrates opposing each other, comprising steps of:

forming a first unevenness on a spacer substrate; and

forming a second unevenness of a smaller cycle period than that of the first unevenness on the spacer substrate on which the first unevenness is formed.

44. (Previously Presented) A method for manufacturing a spacer which defines an interval between substrates opposing each other, comprising steps of:

forming a first unevenness on a spacer substrate; and

forming a second unevenness of a smaller amplitude than that of the first unevenness on the spacer substrate on which the first unevenness is formed.

45. (Previously Presented) The method according to claim 44 or 45, wherein

the step of forming the first unevenness is a chemical processing.

46. (Previously Presented) The method according to claim 45, wherein the chemical processing is an anode oxidation process.
47. (Previously Presented) The method according to claim 43 or 44, wherein the step of forming the second unevenness is non-chemical processing.
48. (Previously Presented) The method according to claim 47, wherein the non-chemical processing is mechanical processing.
49. (Previously Presented) The method according to claim 48, wherein the mechanical processing is a grading processing.
50. (Previously Presented) The method according to claim 43 or 44, further comprising:
a step of forming a high resistivity film on the spacer substrate, after the step of forming the second unevenness.
51. and 52. (Canceled)

53. (Previously Presented) A method of manufacturing an electron beam generating apparatus comprising a first substrate having an electron-emitting element, a target irradiated with an electron emitted from the electron-emitting element, a second substrate disposed in opposition to the first substrate and a spacer defining an interval between the first and second substrates, the method comprising steps of:

- forming a spacer; and
- disposing the spacer between the first and second substrates,

wherein the step of forming the spacer comprises the steps of:

- forming a first unevenness on a spacer substrate; and
- forming a second unevenness of a smaller cycle period than that of the first unevenness on the spacer substrate on which the first unevenness is formed.

54. (Previously Presented) A method of manufacturing an electron beam generating apparatus comprising a first substrate having an electron-emitting element, a target irradiated with an electron emitted from the electron-emitting element, a second substrate disposed in opposition to the first substrate and a spacer defining an interval between the first and second substrates, the method comprising steps of:

- forming a spacer; and
- disposing the spacer between the first and second substrates,

wherein the step of forming the spacer comprises the steps of:

- forming a first unevenness on a spacer substrate; and

forming a second unevenness of a smaller amplitude than
that of the first unevenness on the spacer substrate on which the first unevenness is formed.

55. (Canceled)